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# Influence of annealing on Si-Ge thin films with high concentration of tellurium and zinc

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**Abstract:**

The elements are distinguished via the basis of energy band gap. Two configurations $Si_{10}Ge_{10}Te_{80}$ and $Si_{10}Ge_{10}Zn_{80}$ multilayers were annealed under vacuum at eutectic temperature of 400 °C to form alloys between the deposited layers. The two samples were studied at different temperatures to improve the physical properties of the thin films. Kinetics of the two configurations $Si_{10}Ge_{10}Te_{80}$ and $Si_{10}Ge_{10}Zn_{80}$ were studied in the temperature range 308- 673 $^{o}$K. The results revealed that the crystallization of the thin film of multilayer for the samples increases with increasing the annealing temperature and increasing the zinc content. The influence of annealing on the structure and stability of the samples has been studied by X- ray diffraction. The optical and electrical measurements were carried out after annealing. The electrical conductivity of the two samples was measured as a function of temperature and annealing time. It was found that the electrical conductivity for $Si_{10}Ge_{10}Zn_{80}$ increases, and the optical gap decrease due to the crystallization effects that occurs only in Ge matrix and with increasing zinc content at high concentration.

**Keywords:** thin films, annealing, temperature, crystallization, optical gap, electrical conductivity.

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# الرقيقة ذات التركيز العالي من التيلوريوم والزنك (Si-Ge)تأثير التلدين على أغشية

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## الملخص

يتم تمييز العناصر من خلال فجوة نطاق الطاقة الأساسية. تم التلدين بتكوينين Si10Ge10Te80 و Si10Ge10Zn80 متعدد الطبقات تحت فراغ عند درجة حرارة سهلة الانصهار تبلغ 400 درجة مئوية لتشكيل سبائك بين الطبقات المودعة. تمت دراسة العينتين عند درجات حرارة مختلفة لتحسين الخواص الفيزيائية للأغشية الرقيقة. تمت دراسة حركية التكوينين Si10Ge10Te80 و Si10Ge10Zn80 في المدى الحراري 308-673 درجة مئوية. أظهرت النتائج أن تبلور الطبقات الرقيقة للعينات يزداد مع زيادة درجة حرارة التلدين وزيادة محتوى الزنك. تمت دراسة تأثير التلدين على بنية وثبات العينات باستخدام حيود الأشعة السينية. تم إجراء القياسات الضوئية والكهربائية بعد التلدين. تم قياس التوصيل الكهربائي للعينتين كدالة لدرجة الحرارة وزمن التلدين. وجد أن الموصلية الكهربائية لـ Si10Ge10Zn80 تزداد، وتقل الفجوة الضوئية بسبب تأثيرات التبلور التي تحدث فقط في مصفوفة Ge ومع زيادة محتوى الزنك عند التركيز العالي.

**الكلمات المفتاحية: الأغشية الرقيقة، التلدين، درجة الحرارة، التبلور، الفجوة الضوئية، التوصيل الكهربائي.**

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## 1.Introduction

The.modern.technological.era.started.with.the.invention.of.the.transistor.and.the.birth.of.solid.state.electronics..From.that.date,.we.have.been.rapidly.developed.the.science.and.technology.based.firstly.on.germanium,.then.on.silicon,.and.later.on.multilayers.for.elements.with.germanium,.and.silicon.The.necessity.to.save.weight.and.ratio.of.element,.and.to.improve.the.electrical.conductivity.in.the.function.of.the.devices,.stimulated.an.intense.research.activity.to.obtain.the.thin.films.from.multilayers..In.the.same.time,.the.worldwide.interest.was.moved.from.electronic.to.more.complex.optoelectronic.applications..Taking.into.account.these.big.tasks.,.the.class.of.materials.must.be.enlarged,.new.materials.with.new.properties.must.be.prepared..The.physical.properties..of.thin.films.materials.of.many.semiconductors.and.elements.has.been.investigated.[18]..

The.improvement.of.devices.based.on.the.prepared.materials.via.different.high.technology.fields.of.science..Nowadays,.commercial.devices.require.the.development.of.tailored.materials..Approaches.to.evaluate.the.physical.properties.of.their.structures.produces.an.inevitable.industrial.delay.in.the.devices.improvement..Moreover,.with.the.trend.to.continuous.curing.of.the.components.makes.it.becomes.necessary.to.deal.with.the.spatial.resolution.problem..For.the.advance.in.such.applications,.the.locally.investigation.of.the.change.in.the.electrical.conductivity.with.temperature.and.elements.contents.of.in.new.compounds.of.materials.is.therefore.a.key.issue.

Materials.are.commonly.affected.by.a.large.concentration.of.point.defects,.hence.the.heat.treatment.are.very.important..The.transition.of..crystalline.state.proceeds..by.nucleation.and.growth..reactions,.a.systematic.study.on.the.kinetics.of.the.crystal.phase.remains.one.of.the.most.interesting.aspects.of.physics.properties.[7]..

A.strict.control.on.the.ratio.of.materials.and.location.is.necessary,.but.also.because.their.behavior.in.the.material.structure.is.still.rather.unclear..Electrical.conductivity.may.also.be.used.to.investigate.of.crystallization.for.material.of.thin.films.and.type.of.elements.[9].

The.aim.of.this.work.is.to.study.the.physical.properties.of.the.thin.film

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s.for.multilayers.and.using.the.results.to.investigate.affects.on.the.electrical.conductivity.with.annealing,and.high.concentration.of.materials.contents.

**II.Experimental**

Two.configurations.of.multilayers.were.deposited.using.Edwards.306.thermal.evaporator.under.vacuum.of.$6\times10^{5}$.mbar.on.borosilicate.glass.substrates..The.first.configuration.consists.of.silicon(Si),.germanium.(Ge),.and.tellurium.(Te),.and.the.second.configuration.consists.of.silicon.(Si),.germanium.(Ge),.and.Zinc.(Zn)..The.Two.samples.prepared.at.80°C...The.first.sample.in.this.configuration.is.$Si_{10}Ge_{10}Te_{80}$.and.the.thicknesses.of.layers.of.this.sample.are.30.nm.of.Si,.30.nm.of.Ge,.and.240.nm.of.Te..The.second.sample.in.this.configuration.is.$Si_{10}Ge_{10}Zn_{80}$.and.the.thicknesses.of.layers.of.this.sample.are.30.nm.of.Si,.30.nm.of.Ge,.and.240.nm.of.Zn..The.samples.of.the.two.configurations.are.then.annealed.under.vacuum.at.eutectic.temperature.of.400.°C.to.form.alloys.between.the.deposited.layers..The.following.table.shows.the.prepared.samples..The.total.film.thickness.measured.by.the.Dectak.surface.profiler.was.in.the.range.of.300nm.

The.crystallinity.of.the.two.samples.was.measured.by.Xray.diffractometer.(.Model:.Labx.XRD6100.).provided.by.copper.(Cu).Xray.tube.of.wavelength.$\lambda=1.54$**Å**.was.used.for.structue.analysis.of.the.thin.films**..**The.interplaner.distance.was.determined.using.Bragg`s.Equation:$2d.\sin\theta.=.n.\lambda$

Where.d.is.the.interplaner.distance.and.$\theta$.is.the.angle.of.x-ray.diffraction.

JASCO.V630.UVVIS.Spectrophotometer.was.used.for.transmission.and.absorption..measurements..A.cryostat.(.photon.cryostat.220.Ohmmetry.).was.used.for.electrical.measurements.The.sample.is.maintained.between.two.electrodes.as.a.coplanar.structure.attached.to.a.dc.voltage.of.60.Volt..The.pressure.is.about.$6\times10^{3}$.mbar,.depending.on.the.geometry.of.the.vacuum.chamber..The.substrate.holder.is.provided.by.heating.system.to.raise.the.temperature.of.the.sample.up.to.60 °C.

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## III.Results.and.discussion

### 1.The.Xray.diffraction.(XRD)

The.structural.properties.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.prepared.at.80°C.and.annealed .at.400°C.for.have.been.investigated. by.XRD..The.phases.appeared.in.the. xray.spectra.are.GeGe(111),.GeGe(211),.GeGe(220).for.sample.$Si_{10}Ge_{10}Zn_{80}$.and.phases.appeared.in.the.x.ray. spectra.are.GeGe(111),GeGe(211).for.sample.$Si_{10}Ge_{10}Te_{80}$.The.inter.planer.distances.(dspacing).have.been.calculated.using.the.Bragg`s.equation.and.are.given.in.table.(1)..

Table(1):.The.dspacing.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.prepared.at.80°C.after.annealing .at.400°C.for.2h.

| Phases | (2θ).°2Theta. | d-Spacing.(Å) | $h^2+k^2+l^2$ | Orientations | Lattice constant.(Å) | Lattice.Constant.(Å).in.text.book.[10-11]. |
|---|---|---|---|---|---|---|
| Ge(111) | 26.889 | 3.311 | 3 | (111) | 5.736 | 5.74 |
| Ge(211) | 38.626 | 2.328 | 6 | (211) | 5.702 | 5.6575.and.5.74 |
| Ge(220) | 44.953 | 2.014 | 8 | (220) | 5.700 | 5.6575.and.5.74 |

It.is.clear.from.x.ray.analysis.of.the.tw.sampe.that.crystallization.effects.occur.only.in.Ge.matrix.because.the.crystallizing.temperature.of.the.germanium.(abut. 300°C).is.lower.than.that.of.silicon.(.about.500ºC.)..This.also.indicates.that.zinc.atoms.are.located.between.crystalline multilayers,.that.atoms.also.conformational.bonds.with.the.surrounding.atoms..

Therefore..it.has..a.good.bond..and..reduces..crystal.defects..and..increases..electrical.conductivity.,.where.the.crystallization.effects.occur.in.the.sample. $Si_{10}Ge_{10}Zn_{80}$.more.than.the.crystallization.occur.in.the.sample.$Si_{10}Ge_{10}Te_{80}$.

### 2.Optical.Properties

In.this.section.we.will.discuss.the. measurements.of.transmission.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.prepared.at.80°C,.and.the.deduced.optical.energy.gap.after.annealing.at.400°C.

#### 2..1..Transmission.and.absorption. measurements.

Figures.(1).show.transmission.for.the .$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.thin.films.after.annealing.atm400°C..It .is.clear.that.for.high.energies.($\lambda_{min}$).there.is.no.transmission.appeared.for.samples.but.for.low.energies.($\lambda_{max}$).the.transmission.is.high..For.low.energies.($\lambda_{max}$).h

owever.there.are.no.appropriate.electronic.transitions.possible.so.transmission.is.very.high.in.this.range..It.is.not.100%.however,.because.of.absorption..The.interpretation.of.the.transmission.spectra.in.figure.(1).is.not.so.straight.forward..For.high.energies,.where.absorption.is.high.according.to.the.transmission.chart,.increases.as.well..This.can.only.be.explained.by.a.theoretical.treatment.of.the.interaction.between.light.and.matter.[12.14].

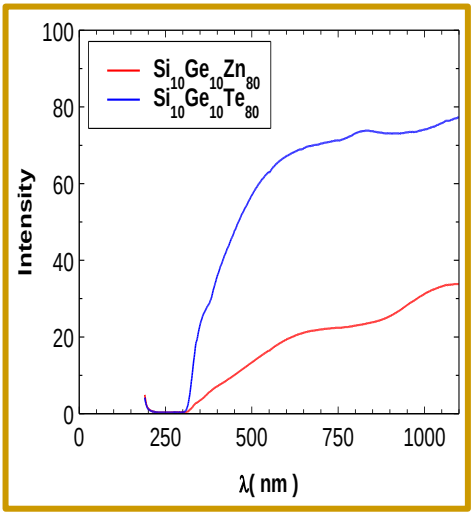


Figure.(1):.Transmission.spectra.for.untreated.the.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.prepared.at.80°C.and.annealed.at.400ºC.for.2.h.It.is.shown.that.for.high.energies.($\lambda_{min}$).there.is.no.transmission.for.film.$Si_{10}Ge_{10}Te_{80}$.,but.for.film.$Si_{10}Ge_{10}Zn_{80}$.the.transmission.is.about.34%..For.high.energies.($\lambda_{min}$),.where.absorption.is.high.according.to.the.transmission.chart..After.annealing.at.400ºC,the.absorption.is.increases.due.to.the.increasing.of.crystallization.and.the.high.concentration.of.zinc.(Zn).which.leads.to.a.decrease.of.the.transmission.intensity...

**2.2..Optical.energy.data**

The.optical.band.gap.is.useful.material.parameter..It.allows.to.compare.between.the.samples.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.based.materials.regarding.their.light.absorption.properties.[15.17]..The.concentration.of.tellurium.and.zinc.plays.an.important.role.for.determining.electrical.conductivity.and.the.optical.energy.gap.for.the.samples.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.,as.conformed.by.the.results.obtained.in.previous.works[18]..Figures.(2)..shows.the.relation.between.$(\alpha h\nu)^{1/2}$.and.$(h\nu)$.for.the.two.samples..According.to.Tauc's.relation.[19],.the.optical.energy.gaps.were.deduced.from.the.plots,.and.the.values.are.given.in.tables.(2).for.the.two.samples.after.annealing..

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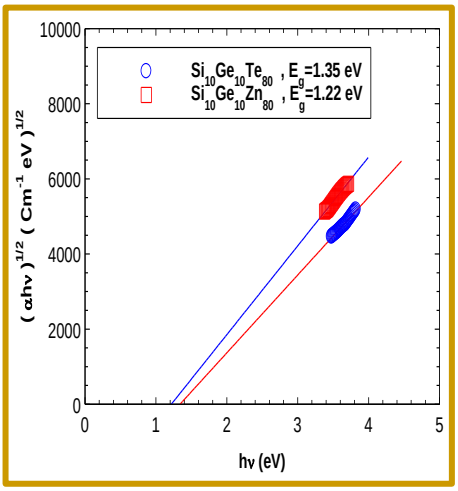


Figure.(2):.$(\alpha h\nu)^{1/2}$..Vs..hν.for.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.prepared.at.80ºC.and.annealed.at.400°C.for.2.h.

The.data.shows.that.the.optical.energy.gap.is.decreases.with.raising.and/or.annealing.temperature.and.due.to.crystallization.effects.in.Ge.matrix.[20,23].,and.partially.due.to.high.concentration.of.zinc.(.Zn.).

Table.(2):.The.data.of.optical.band.gap.$E_g$.for.untreated.samples.

| The.sample | $E_g$.(eV.) |
|---|---|
| $Si_{10}Ge_{10}Te_{80}$ | 1.35 |
| $Si_{10}Ge_{10}Zn_{80}$ | 1.22 |

**3.Electrical.properties**

**3.1..Effects.of.temperature.and.(tellurium/zinc).high.concentration.on.the.electrical.conductivity.**

The.conductivities.as.a.function.of.temperature.for.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.prepared.at.80ºC.and.annealed.at.400°C.for.2.h..Here,.the.concentration.of.Te.and.Zn.are.80%,.in.the.temperature.range.308.473.K.are.shown.in.figures.(3).It.is.seen.that.the.relation.between.the.electrical.conductivity.and.the.temperature.obey.the.Arrhenius.type.equation:$\sigma=\sigma 0.\exp(Ea/kBT)$.(1)

where.σ.is.electrical.conductivity,.Ea.is.the.activation.energy.and.kB.is.the.Boltzmann`s.constant..The.high.concentration.for.elements.conducting.are.playing.an.important.role.for.determining.electrical.conductivity.of.multilayers.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films..The.electrical.conductivity.measured.at.308.K.and.the.activation.energy.calculated.from.the.slopes.of.the.lines.for.the.samples.are.given.in.table.(3)..It.is.seen.that.the.electrical.conductivity.increases.while.activation.energy.decreases.with.increasing.the.content.of.(.Zn.).more.

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than.(.Te.).as.conformed.by.the.previous.works.[18,22,23]..

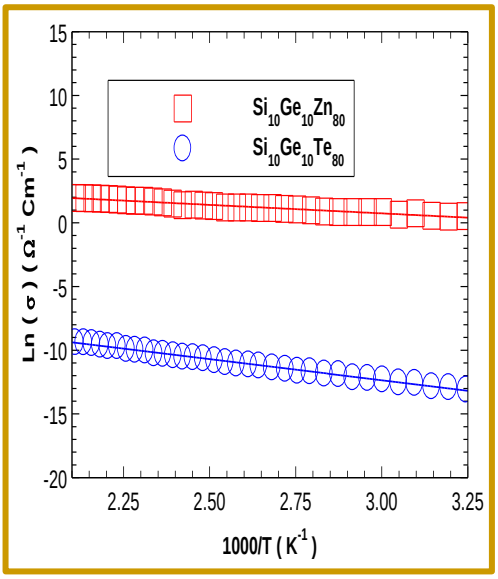


Figure.(3):.Dark.conductivity.vs..inverse.of.temperature.for.multilayers.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.

Table.(3):.Conductivity.measured.at.308.K.and.the.activation.energy.for.untreated.multilayers.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.

| The.sample | concentration.(80%) | $\sigma(\Omega^{-1}.cm^{-1}.)$. | $E_a$.(.eV.) |
|---|---|---|---|
| $Si_{10}Ge_{10}Te_{80}$ | Te | $26\times10^{-3}$ | **0.29** |
| $Si_{10}Ge_{10}Zn_{80}$ | Zn | $31\times10^{-2}$ | **0.12** |

### 3.2..Kinetics.and.thermal.stability

The.electrical.conductivity.of.multilayers.of.$Si_{10}Ge_{10}Te_{80}$.and.$Si_{10}Ge_{10}Zn_{80}$.thin.films.as.a.function.of.annealing.times.were.recorded.at.different.temperatures.473,573.and.673.K.is.given..figure.(4).and.(5),.respectively..All.samples.show.the.same.general.behavior.where.the.electrical.conductivity.increases.with..increasing.the.annealing.time..at.constant.annealing..temperature.and.becomes.constant.at.high.annealing.time..This.behavior.is.attributed.partially.to.crystallization.occurring.in.the.multilayers,.that.crystallization.effects.occur..only.in.Ge.matrix.with.annealing..temperature..and..annealing.time..as..confirmed.by.Xray.data,..and.also.depending.on.the.incorporation.of.zinc.or.tellurium.at.the.network.

It.is.known.that.the.conductivity.of.crystalline.material.is.higher.than.that.of.amorphous.one.since.the.ordered.systems.exhibit.lower.activation.energy.than.the.amorphous.one.[24].The.study.confirms.that.electrical.conductivity.increases.with.increases.at.high.concentration.of.the.element.doping..This.is.clearly.for.the.sample.doped.with.zinc.at.high.concentration,.more.than.for.the.sample.doped.with.tellurium..Thus..the.electrical.cond

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uctivity..measurements..as.a.function ..of..annealing..time.at.constant..tem perature..are.used.to..study.the.isothe rmal.crystallization..kinetics.using.Jo hnson.Mehl.Avermi`s.(JMA).equatio n..

Thus.the.electrical.conductivi ty.measurements.as.a.function.of.ann ealing.time.at.constant.temperature.a re.used.to.study.the.isothermal.crysta llization.kinetics.using.Johnson-Mehl-.Avermi`s.(JMA).equation.in.t he.form[25]:.

$\chi.=.1.-.exp[-kt^n]..(2)$

Where.$\chi$.is.the.volume.fractio n.of.the.crystalline.phases.transforme d.from.the.amorphous.state.at.time.t,. n.refers.to.the.order.of.reaction.and.k .is.the.effective.overall.reaction.rate,. which.actually.reflects.the.rate.of.cry stallization.[26,.27].

The.electrical.conductivity.as .a.function.of.annealing.time.the.volu me.fraction.$\chi$.is:.

$\chi.=.(Ln.\sigma_a.-.Ln\sigma_t)/(Ln\sigma_a.-.Ln\sigma_c)..(3)$

Where.$Ln\sigma_a$.is.logarithm.of.th e.electrical.conductivity.at.zero.time. (activation.electrical.conductivity),.L n.$\sigma_t$.logarithm.of.the.electrical.condu ctivity.at.any.time.t.and.ln.$\sigma_c$.is.logar ithm.of.the.electrical.conductivity.at. the.end.of.saturation.(full.crystallizat ion).

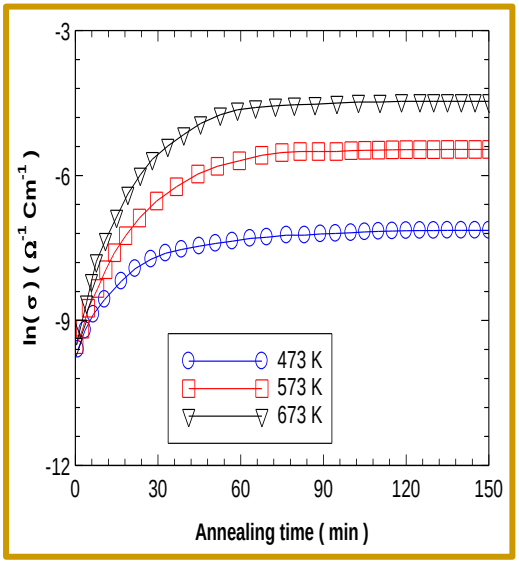


Figure.(4):.logarithm.of.the.el ectrical.conductivity.versus.the.anne aling.time.at.constant.temperatures.f or.$Si_{10}Ge_{10}Te_{80}$.multilayers.

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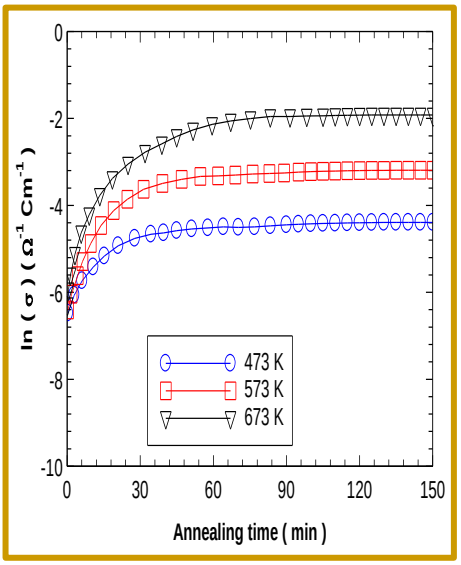


Figure.(5):.logarithm.of.the.electrical.conductivity.versus.the.annealing.time.at.constant.temperatures.for.$Si_{10}Ge_{10}Zn_{80}$.multilayers.

**IV.Conclusions**

The.samples.show.the.same.general.behavior.where.the.electrical.conductivity.increases.with..increasing.the.annealing.time.at.constant.annealing..temperature..and..becomes.constant.at.high.annealing.time..This.behavior.is.attributed.partially.to.crystallization.occurring.in.the.multilayers,.especially.for.germanium.atoms.depending.on.the.annealing.temperature.and.annealing.time.as.confirmed.by.Xray.dat,.and.due.to.the.incorporation.of.zinc.or.tellurium.to.the.network..The.elements.of.dopes.at.high.concentration.plays.an.important.role.for.determining.the.electrical.conductivity.and.optical.ga.in.this.study.the.conductivity.are.(ptype).similarly.for.holes..The.reason.in.changing.optical.gap,.this.may.be.due.to.shifting.the.Fermi.level,.where.increasing.shifting.the.Fermi.level.to.wards.the.valence.band.upon.zinc.or.tellurium.doping.in.the.thin.films..

It.was.found.the.electrical.conductivity.increasing..and.the.optical.gap.decreasing.with.the.crystallization..effects.occur.only.in..Ge.matrix.and.with..increasing.zinc.at.high.concentration..Where.the.optical.gap.change.from.1.35eV.to1.22eV.at.high.concentration.for.tellurium.and.zinc.respectively..It.is.clear.that.the.change.of.the.electrical.conductivity.with.annealing.time.at.different.isotherms.is.one.of.the.sensitive.physical.properties.to.reflect.the.change.and.growth.of.the.phase.transformation.process.of.any.material

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**References**

[1].C.N.R.Rao.and.K.J..Rao,.phase.transformation.in.solids,.91(1978)..
[2].D.Rurnbull,.solid.state.physics.e.seitz.and.turnobull.,.Accademic.press.New.York,.3(1959).
[3].M..Avrami,Chem..Phys.7,1103(1939).
[4].M.K..El-Mously.and.M.M.El-Zaidia,.J..Non-cryst-solids.27,265(1978).
[5].M.M.El-Zaidia.and.A.M.Nassar,.physics.and.chemistry.of.glasses.22,147(1981).
[6].M.M.El-Zaidia,.Ind,.J..Tech.,18,299.(1980).
[7].Deepika,K..S..Rathore,N..S..Saxena,New.Journal.of.Glass.and.Ceramics,.2,1(2012)..
[8].C.N.R..Rao.and.K.J..Rao,.phase.transformation.in.solids.93(1978)..
[9].J.N..Hay,.Brit..Polym..J,.374(1971).
[10].M..S..Abo.Ghazala,.E..Aboelhasn,.A..H..Amar,.and.W..Gamel,.Phys.Status.Solidi.C.8,.No..11–12,.3095–3098.(2011).
[11].B..Tillack,.P..Zaumseil,G..Morgenstern,.D..Kruger,.B..Dietrich,.G..Ritter,Journal.of.Crystal.Growth,.Vol..157,.pp..181-184.(1995).
[12].Z..Remes,.Ph.D.Thesis,.Faculty.of.Mathematics.and.Physics.of.the.Charles.University.Institute.of.Physics.of.the.Academy.of.Sciences.of.the.Czech.Republic,.Prague.(1999).
[13].B..Thangaraju,.and.B..Kalliannan,.J.Cryst..Res.Technol..35,.71(2000)
[14].O..Stenzel,The.Physics.of.Thin.Film.Optical.Spectra,.(Springer-Verlag,.Berlin,.Heidelberg.,.Germany).Press.(2005).
[15].J..M..Zahler,..A..Fontcuberta.Morral,.M..J..Griggs,.H..A..Atwaterand.Y..J..Chabal,.Phys..Rev..B.75,.35309.(2007).
[16].K..W..Jobson.and.J.P.R..Wells,R.E..I..Schropp,N.Q..Vinh,J.I..Dijkhuis,.J.Appl..Phys..103,.13106.(2008).
[17].Mursai,.S..Amiruddin,.I..Usma.T.Winata,.Sukirno,.and.M..Barmawi,Asian.J..Energy.Environ,.Vol.5,.Issue3,.pp..211-222.(2004).
[18.].Masheal.Ali.Alghamdi,.**Master.of.Science.,.**Department.of.Physics,.

The.University.of.King.Saud.University.(2008).
[19].J..Tauc,.in.Amorphous.and.Liquid.Semiconductors,.ed.(J..Tauc,.Plenum).159.(1974).
[20].Z..Li,.Ph.D.Thesis,.Iowa.State.Univerisity,.Ames,.Iowa.(2013).
[21].C..Wang,.D..Wuu,.S..Lien,.Y..Lin,.C..Liu,.C..Hsu,.and.C..Chen,.International.Journal.of.Photoenergy,.Vol 2012,.p..6.(2012).
[22].M..S..Abo.Ghazala,.P.hys..Status.Solidi.C.8,.3099–3102.(2011).
[23].C..Miha.,F..Sava,I..D..Simand.alca,.I..Burducea,.N..Becherescu.&.A. Velea,.Scientifc.Reports,.**11**:.11755..(2021).
[24].A..A..Langford,.M..L..Fleet,.B..P..Nelson,.W..A..Lanford.and.N..Maley,.Phys..Rev..B.45,.13367.(1992).
[25].J..A..Augis,.J..E..Bennett,.J..Thermal.Anal..13,.283.(1978).
[26].M..M..EL-Zaidia,.A..Shafi,.A.A.Ammar,.M..Abo.Ghazala,.J..Mat..Sci..22,.1618.(1987)
[27].Pradeep,.N.S..SaxenaA..Kumar. .Physica.Scripta.54,.207.(1996)